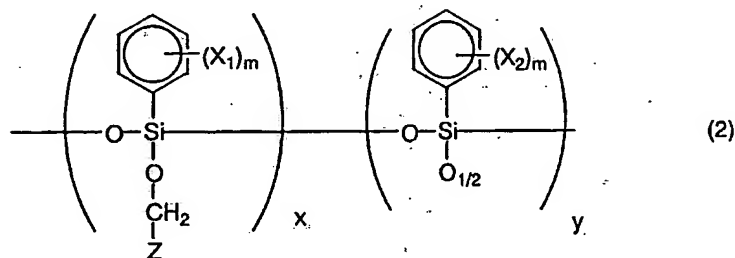


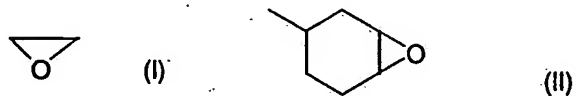
Amendments to the Claims:

Please cancel Claims 1 – 4.

5. (Original) A photosensitive composition for optical waveguides comprising an organic oligomer and a polymerization initiator, said organic oligomer being a silicone oligomer represented by the following formula (2):



wherein X_1 and X_2 may be the same as or different from each other, and denote hydrogen, deuterium, halogen, an alkyl group or an alkoxy group; m is an integer from 1 to 5; and Z denotes an epoxy group shown in the following formula (I) or (II):



wherein x and y designate the proportion of respective units, and y is smaller than x and may be 0.

6. (Original) A method of producing said photosensitive composition for optical waveguides as claimed in Claim 5, said method comprising the steps of:

heating a silicone oligomer in the presence of a solid catalyst; and

filtering said solid catalyst, concentrating filtrate, and further adding polymerization initiator.

7. (Original) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;

irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and

directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides as claimed in Claim 5 is used as said photosensitive composition for optical waveguides.

Please cancel Claims 8 – 20.